Amendments to the Claims:

This listing of claims will replace all prior versions, and listings of claims in the application.

Listing of Claims:

- 1. (Original) A die with text deposited upon the die using semiconductor processing techniques, the die comprising:
 - a substrate which is cut from a wafer comprising a plurality of substrates;
 - a first paragraph in contact with the substrate; and
- a second paragraph in contact with the substrate and aligned with the first paragraph in a column.
- 2. (Original) The die with text deposited upon the die using semiconductor processing techniques of claim 1, wherein:

the substrate is a semiconductor substrate; and

text in the column is comprised of one or more of a metal, an oxide, a polysemiconductor and a photoresist.

- 3. (Original) The die with text deposited upon the die using semiconductor processing techniques of claim 1, wherein the first and second paragraphs are comprised of a plurality of characters.
- 4. (Original) The die with text deposited upon the die using semiconductor processing techniques of claim 3, wherein each of the plurality of characters is comprised of a plurality of primitives.

- 5. (Original) The die with text deposited upon the die using semiconductor processing techniques of claim 1, the die further comprising:
 - a first character appearing in a first color; and a second character appearing in a second color.
- 6. (Original) The die with text deposited upon the die using semiconductor processing techniques of claim 1, the die further comprising an image on the substrate.

7-34. (Cancelled)

- 35. (New) The die with text deposited upon the die using semiconductor processing techniques of claim 1, the die further comprising a third paragraph on the substrate, wherein the second and third paragraphs are arranged in two columns on the substrate.
- 36. (New) The die with text deposited upon the die using semiconductor processing techniques of claim 1, wherein:
 - a radiation source operatively engages the substrate; a mask is generated from an electronic file; the mask operatively engages the radiation source and the substrate; and the mask includes a first and second paragraphs arranged in a column.
- 37. (New) The die with text deposited upon the die using semiconductor processing techniques of claim 1, further comprising a silhouette image in contact with the substrate and at least partially overlapping with at least one of the first or second paragraphs.
- 38. (New) A die with non-functional information deposited upon the die using semiconductor processing techniques, the die comprising:
 - a substrate which is cut from a wafer comprising a plurality of substrates;
 - a first paragraph deposited upon the substrate; and
- a second paragraph deposited upon the substrate and aligned with the first paragraph in one or more columns.

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39. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, wherein the first paragraph is derived from an electronic file that comprises a plurality of elements corresponding to characters for the first paragraphs.

- 40. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 39, wherein each character of the first and second paragraphs is comprised of a plurality of rectangles wherein one side of the rectangle is equal in size to the process resolution.
- 41. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, wherein the first and second paragraphs are separated by at least one of: a hard return, a tab or an enlarged character.
- 42. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, the die further comprising:

a first character visible as a first color; and a second character visible as a second color, which is different from the first.

- 43. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, further comprising a silhouette image in contact with the substrate and at least partially overlapping with at least one of the first or second paragraphs.
- 44. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, wherein:

the first paragraph is read from an electronic source; the second paragraph is read from the electronic source; and the column is generated with an electronic file.

- 45. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, wherein the first paragraph is deposited using a lithographic technique that includes a mask.
- 46. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, wherein the first paragraph is produced with a method comprising steps of:

converting a first character of the first paragraph into a first pattern; converting a second character of the first paragraph into a second pattern; and aligning the first and second characters on a line.

- 47. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, wherein the substrate is a semiconductor wafer.
- 48. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, wherein the first paragraph is produced with a method comprising a step of determining an end of a first line and beginning a second line.
- 49. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, wherein the column is produced with a method comprising a step of determining an end of the first paragraph and beginning the second paragraph on the next line of the column.
- 50. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, wherein the column is produced with a method comprising a step of detecting an end of a first column and depositing a next line in a second column.

51. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 38, wherein the first paragraph is produced with a method comprising steps of:

determining a first color for a first character; and determining a second color for a second character.

52. (New) A die with non-functional information deposited upon the die using semiconductor processing techniques, the die comprising:

a substrate which is cut from a wafer comprising a plurality of substrates arranged in a grid of the wafer;

a paragraph photolithographically deposited upon the substrate; and a silhouette image in contact with the substrate and at least partially overlapping with the paragraph.

- 53. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 52, wherein the paragraph is derived from an electronic file that comprises a plurality of elements corresponding to characters for the paragraphs.
- 54. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 52, wherein each character of the paragraph is comprised of a plurality of rectangles wherein one side of the rectangle is equal in size to the process resolution.
- 55. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 52, the die further comprising:
 - a first character visible as a first color; and a second character visible as a second color, which is different from the first.

56. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 52, wherein:

the first paragraph is read from an electronic source; the second paragraph is read from the electronic source; and the column is generated with an electronic file.

- 57. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 52, wherein the first paragraph is deposited using a lithographic technique that includes a mask.
- 58. (New) A die with non-functional information deposited upon the die using semiconductor processing techniques, the die comprising:

a substrate which is cut from a wafer comprising a plurality of substrates arranged in a grid of the wafer;

a first paragraph photolithographically deposited upon the substrate;
a second paragraph photolithographically deposited upon the substrate; and
a silhouette image in contact with the substrate and at least partially overlapping
at least one of the first or second paragraphs.

- 59. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 58, the die further comprising:
 - a first character visible as a first color; and a second character visible as a second color, which is different from the first.
- 60. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 58, wherein:

the first paragraph is read from an electronic source; the second paragraph is read from the electronic source; and the column is generated with an electronic file.

- 61. (New) The die with non-functional information deposited upon the die using semiconductor processing techniques of claim 58, wherein the first paragraph is deposited using a lithographic technique that includes a mask.
- 62. (New) A die with non-functional information deposited upon the die using semiconductor processing techniques, the die comprising:
- a substrate which is cut from a wafer comprising a plurality of substrates arranged in a grid of the wafer;
- a first paragraph photolithographically deposited upon the substrate, wherein the first and second paragraphs are comprised of a plurality of characters;
- a second paragraph photolithographically deposited upon the substrate wherein at least one of the first or second paragraphs is generated with an electronic file; and
- a silhouette image in contact with the substrate and at least partially overlapping at least one of the first or second paragraphs.